

Coating 114228

Magnetron sputtered system

$HR(0^\circ, (1250-1710)\pm 10\text{nm}) > 99.9\% + R(0^\circ, (1030-1080)\pm 5\text{nm}) < 2\%$

GDD ~ -500...0fs² (GDD optimized for OPO-application)

fig. 1 reflection, 0° unpol.

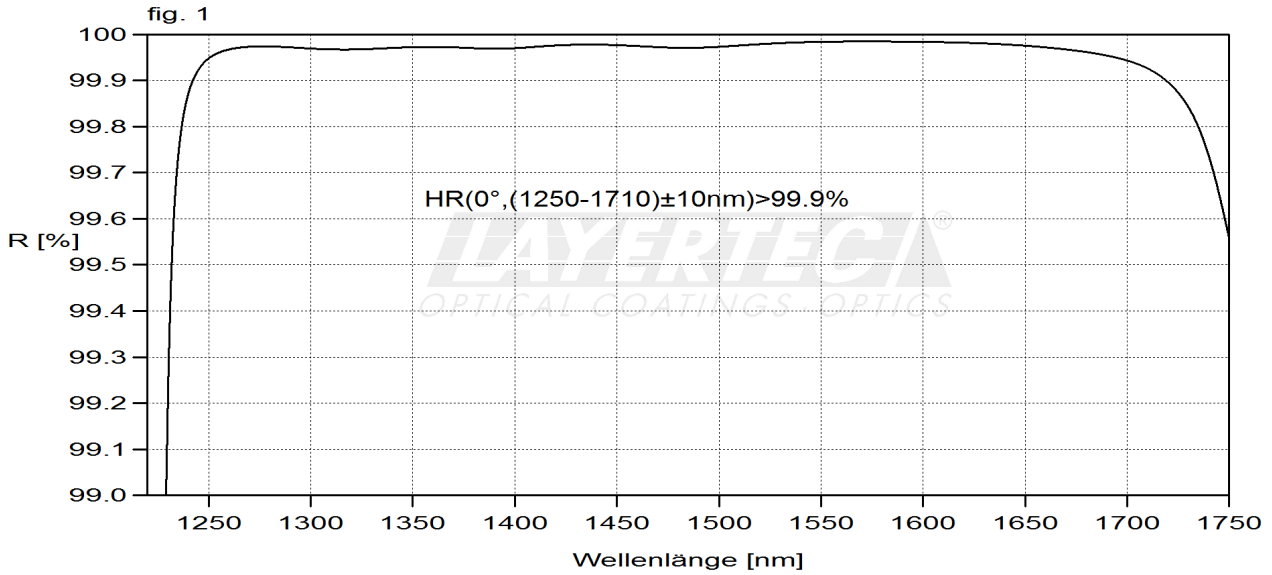


fig. 2 reflection, 0° unpol.

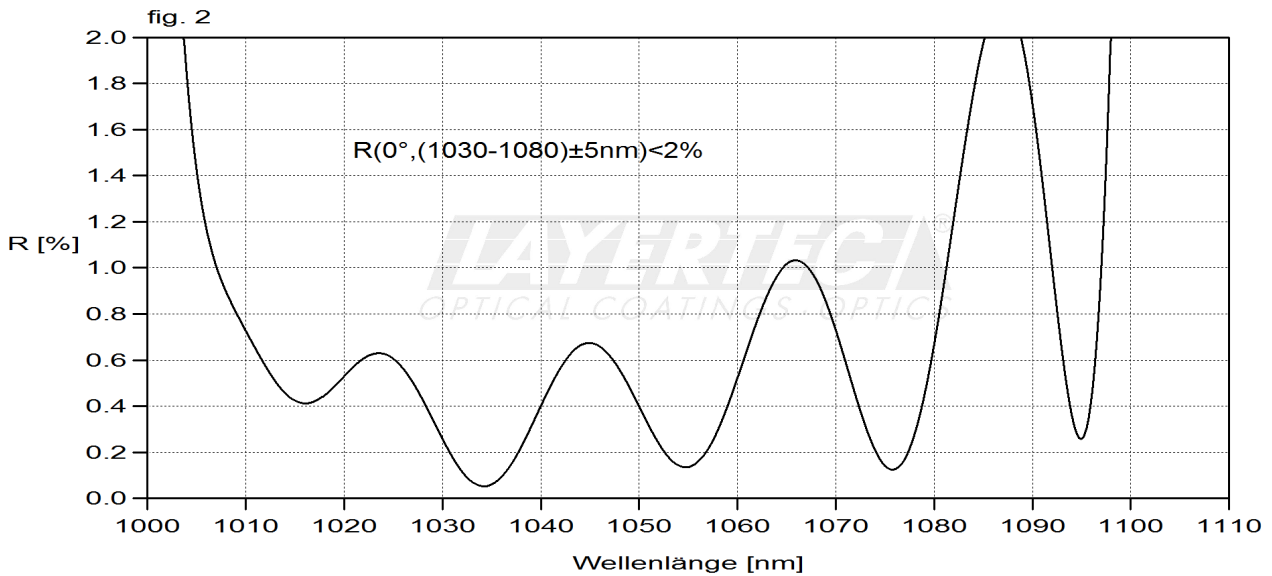


fig. 3 reflection, 0° unpol.

